Reduction of the cell-to-cell variability in Hf$_{1-x}$Al$_x$O$_y$ based RRAM arrays by using program algorithms

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Abstract— In this report, we propose an effective route to reduce the cell-to-cell variability in 1T-1R based RRAM arrays by combining the excellent switching performance of Hf$_{1-x}$Al$_x$O$_y$ with an optimized Incremental Step Pulse with Verify Algorithm (ISPVA) for programming. The strongly reduced cell-to-cell variability improves the thermal and post-programming stability of the arrays, which is relevant for many applications of the RRAM technology. Finally, the retention study at 150 °C enables the prediction of the data storage capability.

Index Terms—RRAM, Hf$_{1-x}$Al$_x$O$_y$, variability, data retention.

I. INTRODUCTION

Resistive Random Access Memories (RRAM) are based on the electrical modification of the conductance of Metal-Insulator-Metal stacks: the set operation switches the cell into a Low Resistive State (LRS), whereas reset operation brings the cell back to a High Resistive State (HRS) [1]. HfO$_2$ based RRAM is one of the most promising technologies for the next generation of non-volatile memory applications [2]. However, the large cell-to-cell variability in RRAM arrays is still a relevant issue. The random conductive filament formation and rupture process is generally regarded as a critical non-uniformity parameter of resistive switching. Ionic doping of HfO$_2$ is one effective way to improve the switching stability of the resistive switching [3]. Using a program algorithm is another option to reduce the resistance variability, although post-programming shifts were reported recently [4]. In this study, we demonstrate the drastic reduction of the cell-to-cell variability and post-programming instabilities using Hf$_{1-x}$Al$_x$O$_y$ as switching oxide and optimized program algorithms with verify procedures.

II. EXPERIMENTAL

The 1T-1R RRAM cells in the 4 kbit arrays are constituted by a NMOS transistor manufactured in IHP’s 0.25 μm CMOS technology, whose drain is connected in series to a variable resistor, as illustrated in Fig. 1. The resistor is a Metal-Insulator-Metal (MIM) device integrated on the metal line 2 of the CMOS process. This MIM resistor consists of a planar TiN/ Hf$_{1-x}$Al$_x$O$_y$/Ti/TiN stack. One additional mask is required for patterning the MIM stack. The Hf$_{1-x}$Al$_x$O$_y$ layers with thickness of 6 nm are grown by Atomic Layer Deposition (ALD with an Al content of 10 %) using an ASM A412 Batch Furnace. After patterning the MIM cells with area of about 0.4 μm$^2$, an additional thin Si$_3$N$_4$ layer was deposited to protect the MIM cell.

Fig. 1: TEM cross-sectional image of 1T1R architecture with a NMOS access transistor (1T, marked by a blue square) and a 0.6×0.6 μm$^2$ MIM cell (1R, marked by a white square); BL, SL and WL denote the bit line, source line and word line, respectively.

III. RESULTS AND DISCUSSION

To activate the resistive switching behavior, the RRAM cells require a preliminary forming operation. This initial operation plays a fundamental role in determining the subsequent devices performance. Therefore, the Incremental Form and Verify (IFV) algorithm is used [5]. The functionality of the forming and programming algorithms has been verified over 1000 cycles on the arrays.

In order to suppress the reported post-program instabilities, the Incremental Step Pulse with Verify Algorithm (ISPVA) was applied [5], consisting of a sequence of increasing voltage pulses on the drain terminal during set operation and on the

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source terminal during reset operation. After every pulse a read and verify operation is performed. Averaged, 6 Voltage pulses with a width of 12 μs are required for the set process, respectively 12 pulses with the same width for resetting the resistive cells.

The determination of the correct threshold values for the ISPVA is a trade-off between high On/Off ratio, high programming yield and low cell-to-cell variability. By simply increasing the On/Off ratio, the cell-to-cell variability will be raised too, while the programing yield will be reduced. In addition, the threshold values are also affected by the choice of the resistive oxide.

In order to determine the optimum threshold values for HfO₂ and Hf₁₋ₓAlₓOₓ, the ISPVA is applied by using the two different LRS thresholds of 18 and 30 μA. Similarly a current value of 5 μA was considered for HRS in order to target a HRS/LRS ratio of 3 respectively 6. The cumulative distributions of the read currents after reset and set programming cycles, using the ISPVA are illustrated in Fig. 2. The variability of the LRS can be optimized by the Al-doping of the HfO₂ layer and by choosing the correct threshold value of 30 μA, as shown in Fig. 2b).

Compared to recently reported distributions [6, 8], the window between HRS and LRS is well defined and the cell-to-cell as well as the cycle-to-cycle variability is strongly reduced.

The mean LRS current values of pure HfO₂ devices tend to increase with the number of cycles [7]. By doping with Al, this trend is eliminated. The current values of HRS and LRS of Hf₁₋ₓAlₓOₓ remain constant during 1000 cycles. Moderate Al-doping of 10% stabilizes the HfO₂ matrix, improving the endurance properties by hindering oxygen-vacancies relaxation without severe change in switching parameters [8]. In addition, the Al-doping of HfO₂ reduces also the variability of the LRS current values, as illustrated in Fig. 3.

The evolution of the mean reset and set voltage values during the 1000 endurance cycles are illustrated in Fig. 4. The voltages values of the reset operation are a bit higher in pure HfO₂ than in Al-doped HfO₂, which is in line with reported trends [7]. The mean voltage values of Hf₁₋ₓAlₓOₓ based cells are not impacted by cycling, while the values of HfO₂ cells are slightly influenced by cycling.

In order to evaluate the post-programming stability, the read-out operation is continued for 100 sec after the HRS or LRS current thresholds are achieved. The programming as well as the reading operation is performed at ~40 °C and 150 °C. The LRS and HRS resistances programmed by ISPVA algorithms are illustrated in Fig. 4. Short time instabilities (< 2 s) are
monitored; a few cross-bit cells are detected in the LRS/HRS window. But after 10 seconds, the HRS distribution reverts back above the threshold value. As shown in Fig 4, there isn’t any remarkable impact of temperature on the relaxation characteristics of the HRS.

Charging effects, filament rearrangement, redistribution of vacancies and dielectric relaxation processes in the restive oxide layer could cause the short time instability effects. The LRS state remains stable after set programming, indicating the absence of filament rearrangements or charging effects. After finishing the reset ISPVA, dielectric relaxation processes could cause the shift of the HRS resistances to lower as well as larger values than the initial HRS resistance [9].

As shown in Fig. 7, the LRS currents continuously decrease with cycling numbers and retention time, which could be caused by oxygen diffusion related mechanism [11]. The degradation of the HRS is different, all currents increase similarly after a short time of baking followed by a more or less stable plateau. They are not additionally degraded by cycling. The number of so-called cross-bit cells; cells which current values shifted in between the threshold values for HRS (5 µA) and LRS (30µA) during the retention stress test are illustrated in Fig. 5.

The data retention of HfO₂ based RRAM devices can be improved by increasing the LRS currents [10]. An alternative approach to improve the retention is using ISPVA for programming HfₓAlₙO₃ cells. The high temperature data retention is investigated at the temperature of 150 °C.

1000 HfₓAlₙO₃ cells were programmed via ISPVA to LRS respectively to HRS then exposed to thermal stress up to 100 hours. The evolution of LRS and HRS distribution was monitored at log spaced sampling times from 0.1 to 100 hours, as illustrated in Fig. 6.

While the number of cross-bit cells in the HRS remains less than 15% of all HfₓAlₙO₃ cells, the percentage of cross-bit cells in LRS is strongly raised by cycling and baking time. The low formation energy of oxygen vacancies in trivalent ion-doped HfO₂, which reduces the variability of switching parameters, could also lead to worse retention results [12]. However, the shorter bond length between Al and O ions reduces also the unwanted diffusion of oxygen vacancies. The trade-off between good retention and low variability has to be balanced by choosing the correct amount of doping.
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